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20th JCF-Frühjahrssymposium, March 2018, Konstanz, Germany

Introduction

Water disinfection with UV-C radiation gets more and more important over the last 20 years. Hg-low-pressure discharge lamps are typically used as artificial UV-C sources. The main emission (85%) of these lamps lays at 254 nm, 12% lays at 185 nm (VUV-region) and 3% in the visible range of the electromagnetic spectrum. Therefore, the majority of the emitted radiation is UV-C light, which can be used directly for water disinfection. The 12% of VUV emission, become absorbed by water under formation of OH-radicals, already in small layer thicknesses. To increase the disinfection efficiency of Hg-low-pressure discharge lamps it is necessary to convert the emitted VUV-radiation into UV-C-radiation. Therefor phosphors are needed, which can be excited with 185 nm and emits radiation between 200 and 310 nm. In addition to disinfection purposes, UV-C radiation can also be used for so called "advanced oxidation processes" (AOP). AOP is a fast growing field in the area of water treatment, in which OH--radicals are used to break C-C and C-H bonds to decompose organic pollutants [1].



Radiation between 200 and 310 nm induces the photochemical dimerization of two adjacent thymine bases by [2+2]-cycloaddition sugar phoshate backbone sugar phoshate backbone



Fig. 5 Relative germicidal efficacy for B. subtilis according DIN 5031-10 and photoluminescence emission spectra of YPO₄:Bi³⁺, YPO₄:Pr³⁺ (λ_{Exc} = 160 nm)

Conclusions

Future work will deal with the more UV-C emitting phosphors. The herein presented phosphors are already known and multiple studies were dedicated to them.

Literature

[1] R. Andreozzi et al., Cat. Today, 53, 2008, 51-59 [4] A.J.J. Bos et al., Rad. Measure., 43, 2008, 222-226 [2] System SE. The UV/oxidation handbook, 1994 [3] R.H.P. Awater, P. Dorenbos, J. Lumi., 184, 2017, 221-231







